IN THE CLAIMS

1 (Currently Amended). A photoresist comprising:

a photoacid generator that includes a cation with a base atom coupled to at least ~~two~~ three entirely sigma-bonded moieties.

2 (Original). The photoresist of claim 1 including an anion and a cation, wherein said cation does not include phenyl.

Claim 3 (Canceled).

4 (Original). The photoresist of claim 1 wherein said photoacid generator includes a cation with a base atom coupled to at least one sigma-bonded moiety.

5 (Previously Presented). The photoresist of claim 1 wherein said photoacid generator is more transparent than phenyl containing photoacid generators.

6 (Original). The photoresist of claim 1 wherein said photoacid generator includes a cation with a first moiety sigma-bonded to a base atom and a chain coupled to said base atom, said chain in turn coupled by a double bond to second moiety.

7 (Original). The photoresist of claim 6 wherein said second moiety is selected from the group of carbon, nitrogen, sulfur, and phosphorus.

8 (Original). The photoresist of claim 7 wherein said second moiety is coupled to an alkyl or a substituted alkyl.

9 (Original). The photoresist of claim 8 wherein said alkyl or substituted alkyl includes a halogen, ether, ester, carbonate, or ketone.

10 (Original). The photoresist of claim 1 including a photoacid generator including a cation including a base atom coupled to at least two moieties by sigma-bonds, said base atom coupled to a chain in turn coupled to a first moiety, said first moiety coupled through a double bond to a second moiety.

11 (Original). The photoresist of claim 10 wherein said second moiety and said first moiety are selected from the group including carbon, nitrogen, sulfur, and phosphorus.

12 (Original). The photoresist of claim 11 wherein at least one of said first and second moieties includes oxygen.

13 (Original). The photoresist of claim 10 wherein said base atom is sulfur.

14 (Currently Amended). A method comprising:

forming a photoresist with a photoacid generator with a cation having a base atom coupled to at least ~~two~~ three entirely sigma-bonded moieties.

15 (Original). The method of claim 14 including providing a cation to said photoacid generator that does not include phenyl.

16 (Previously Presented). The method of claim 14 including providing an entirely sigma-bonded cation.

17 (Original). The method of claim 14 including forming said photoacid generator of a cation with a base atom coupled to at least one sigma-bonded moiety.

18 (Previously Presented). The method of claim 14 including forming a photoresist with a photoacid generator that is more transparent than phenyl containing photoacid generators.

19 (Original). The method of claim 14 including forming said photoacid generator with a cation having a first moiety sigma-bonded to a base atom and a chain coupled to said base atom, coupling said chain by a double bond to a second moiety.

20 (Original). The method of claim 19 including forming said second moiety from carbon, nitrogen, sulfur, or phosphorus.

21 (Original). The method of claim 20 including forming said second moiety of an alkyl or substituted alkyl.

22 (Original). The method of claim 14 including forming the photoacid generator with a cation having a base atom coupled to at least two moieties by sigma-bonds, said base atom coupled to a chain in turn coupled to a first moiety, said first moiety coupled through a double bond to a second moiety.

23 (Currently Amended). A photoresist comprising:

a photoacid generator including a cation that is entirely sigma-bonded and including a base atom coupled to at least three moieties.

24 (Original). The photoresist of claim 23 wherein said cation includes a base atom coupled by sigma-bonds to at least three moieties.

25 (Original). The photoresist of claim 23 wherein said moieties are alkyl or substituted alkyls.

26 (Original). The photoresist of claim 25 wherein said alkyl or substituted alkyl includes a halogen, ether, ester, carbonate, or ketone.

27 (Original). The photoresist of claim 23 wherein said photoacid generator includes a sulfur atom sigma-bonded to alkyl groups.

28 (Original). The photoresist of claim 24 wherein said base atom is sulfur.